

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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| Applicant | : | Washio et al. |
| Appl. No. | : | 10/560,155 |
| Filed | : | December 9, 2005 |
| For | : | DEVELOPER COMPOSITION FOR RESISTS AND METHOD FOR FORMATION OF RESIST PATTERN |
| Examiner | : | Le, Hoa Van |
| Group Art Unit | : | 1752 |

AMENDMENT AND RESPONSE TO OFFICE ACTION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the final Office Action mailed **May 29, 2007**, Applicants respectfully request consideration of the following amendments and remarks:

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims are reflected in the listing of claims which begins on page 3 of this paper.

Remarks/Arguments begin on page 5 of this paper.